

anti-4-cholesten-3-one, methyloxime derivative

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|-----------------------------|--|
| Inchi: | InChI=1S/C28H47NO/c1-19(2)8-7-9-20(3)24-12-13-25-23-11-10-21-18-22(29-30-6)14-16 |
| InchiKey: | ANJYUACJDKITGZ-ZAZWZDAPSA-N |
| Formula: | C28H47NO |
| SMILES: | CON=C1C=C2CCC3C(CCC4(C)C(C(C)CCCC(C)C)CCC34)C2(C)CC1 |
| Mol. weight [g/mol]: | 413.68 |

Physical Properties

| Property code | Value | Unit | Source |
|---------------|---------|--------|----------------|
| hf | -426.49 | kJ/mol | Joback Method |
| hvap | 82.25 | kJ/mol | Joback Method |
| log10ws | -8.28 | | Crippen Method |
| logp | 8.030 | | Crippen Method |
| mcvol | 369.190 | ml/mol | McGowan Method |
| pc | 893.73 | kPa | Joback Method |
| rinpol | 3163.00 | | NIST Webbook |
| rinpol | 3163.00 | | NIST Webbook |
| tb | 984.33 | K | Joback Method |
| tc | 1217.74 | K | Joback Method |

Sources

| | |
|------------------------|---|
| Crippen Method: | https://www.chemeo.com/doc/models/crippen_log10ws |
| Joback Method: | https://en.wikipedia.org/wiki/Joback_method |
| McGowan Method: | http://link.springer.com/article/10.1007/BF02311772 |
| NIST Webbook: | http://webbook.nist.gov/cgi/cbook.cgi?ID=R417588&Units=SI |
| Crippen Method: | http://pubs.acs.org/doi/abs/10.1021/ci9903071 |

Legend

| | |
|--------------|---|
| hf: | Enthalpy of formation at standard conditions |
| hvap: | Enthalpy of vaporization at standard conditions |

| | |
|-----------------|-------------------------------------|
| log10ws: | Log10 of Water solubility in mol/l |
| logp: | Octanol/Water partition coefficient |
| mcvol: | McGowan's characteristic volume |
| pc: | Critical Pressure |
| rinpol: | Non-polar retention indices |
| tb: | Normal Boiling Point Temperature |
| tc: | Critical Temperature |

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